

REMARKS

This application has been carefully reviewed in light of the Office Action dated June 16, 2005. Claims 1 to 6 and 19 are in the application, of which Claim 1 is independent. Claims 7, 8, 10 to 17, and 20 have been cancelled without prejudice. Claims 1, 6, and 19 have been amended herein. Reconsideration and further examination are respectfully requested.

Applicants have not yet received an indication that the documents cited in the June 21, 2005 Information Disclosure Statement have been considered. It is respectfully requested that the Examiner indicate her consideration of these documents by returning an initialed copy of the Form PTO-1449 that accompanied the Information Disclosure Statement.

Turning to the Office Action, Claims 10 to 15, 17, and 20 were rejected under 35 U.S.C. § 102(e) over U.S. Patent No. 6,407,367 (Ito), Claim 16 was rejected under 35 U.S.C. § 103(a) over Ito, and Claims 1 to 8 and 19 were rejected under 35 U.S.C. § 103(a) over U.S. Patent No. 6,727,191 (Zehavi) in view of Ito. The rejections are respectfully traversed.

Claim 1 recites, *inter alia*, a method for manufacturing an SOI substrate having an HF defect density not more than 0.05 defects / cm².

The Office Action concedes that neither Zehavi nor Ito discloses the above-discussed feature. However, the Office Action asserts that this feature would result from routine experimentation. This assertion is respectfully traversed.

Applicant respectfully submits that there has been no showing of motivation


to modify the applied documents to arrive at the above-discussed feature. Further, Applicant respectfully submits that there has been no showing on the record that this feature constitutes routine experimentation.

The dependent claims are also submitted to be patentable because they set forth additional aspects of the present invention and are dependent from the independent claim discussed above. Therefore, separate and individual consideration of each dependent claim is respectfully requested.

The application is believed to be in condition for allowance, and a Notice of Allowance is respectfully requested.

Applicant's undersigned attorney may be reached in our Costa Mesa, California office by telephone at (714) 540-8700. All correspondence should be directed to our address given below.

Respectfully submitted,



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